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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/605,360	09/25/2003	ERH-KUN LAI	11760-US-PA	2359

31561 7590 03/29/2004

JIANQ CHYUN INTELLECTUAL PROPERTY OFFICE  
7 FLOOR-1, NO. 100  
ROOSEVELT ROAD, SECTION 2  
TAIPEI, 100  
TAIWAN

EXAMINER

KESHAVAN, BELUR V

ART UNIT PAPER NUMBER

2825

DATE MAILED: 03/29/2004

Please find below and/or attached an Office communication concerning this application or proceeding.



## **DETAILED ACTION**

### ***Quayle Action***

This application is in condition for allowance except for the following formal matters:

#### ***Drawings***

The drawings are objected to under 37 CFR 1.83(a). The drawings must show every feature of the invention specified in the claims. In claim 7, the features of forming a lining layer on the substrate to cover the gate structure, drain and source regions and of etching back the lining layer to have the lining layer left on a sidewall of the gate structure are not shown. Therefore, the above features must be shown or the feature(s) canceled from the claim(s). No new matter should be entered.

A proposed drawing correction or corrected drawings are required in reply to the Office action to avoid abandonment of the application. The objection to the drawings will not be held in abeyance.

#### ***Claims***

Dependent claim 7 is objected to because of the following informalities: In claim 7, “after said step of forming said drain extension region and said source extension region and before said step of forming said metal silicide layer, the method further comprises forming a lining layer on said substrate to cover said gate structure, said drain region, and said source region” The examiner suggests to change “said drain extension region and said source extension region” to said drain region and said source region reflecting the independent claim 1. Appropriate correction is required.

Prosecution on the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

A shortened statutory period for reply to this action is set to expire **TWO MONTHS** from the mailing date of this letter.

***Allowable Subject Matter***

The following is a statement of reasons for the indication of allowable subject matter:  
The primary reason for the indication of the allowability of claims 1-11 is the inclusion therein, in combination as currently claimed, of the limitation of a method for fabricating a metal oxide semiconductor field effect transistor wherein the line width of the gate structure is reduced by forming a patterned block on the center of the gate structure and using the patterned block as an etch mask.

***Contact Information***

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Belur V Keshavan whose telephone number is 571-272-1894. The examiner can normally be reached on 8-4:30 Monday to Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Matthew S Smith can be reached on 571-272-1907. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Art Unit: 2825

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Bvk. *YVR*  
March 18, 2004.

Belur V. Keshavan  
Examiner. Art Unit 2825.



MATTHEW SMITH  
SUPERVISORY PATENT EXAMINER  
TECHNOLOGY CENTER 2800